MD simulation study on CN passivation film formation on organic polymer surface

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Background of the study

- Need of low-k materials as insulator in microfabrication
 of semiconductors
 - · organic polymers are candidates for such insulating materials
- Development of inter-atomic potential functions

 the functions used for MD simulations of (H,C,N) system proposed by Yamada and Hamaguchi (Yamada and Hamaguchi; JSAP spring meeting 2004; preprint)
 - Prior MD simulations of (H,C) system

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- H atoms injected break chemical bonds of organic polymer substrates and C atoms are deposited on the substrate surface forming amorphous carbon layers
- speculation ; N atoms also form rigid masks on the substrate surface of organic polymer, i.e., CN mixing layers

Preparation for MD simulations

Poly(1,4phenylene) (PPP) is chosen as a simple model of organic polymer

destruction of benzene rings may be essential for etching process
 of organic polymer substrate

- Modification of some parameters of inter-atomic potential functions
 - some parameters associated with N atoms of Yamada's potential functions are modified so as to represent more realistic chemical bonds including N atoms







Findings
With N atom injections, a CN mixing layer is observed to be formed.
• For N ₂ and N ₂ H injections, CN mixing occurs although formed films are somewhat weaker than those in N injections case
• Injected C atoms are observed to form amorphous carbon layers on the substrate with the new inter-atomic potential functions as in the case of Brenner's functions. (H. Yamada and S. Hamaguchi, J. Appl. Phys. 96 (2004) 6147)